

IN THE CLAIMS:

Please amend claims as follows:

1. (original) A sintered object of silicon monoxide for use as a material for forming silicon oxide thin films, the evaporation residue of which object, as determined by subjecting a sample thereof to thermogravimetry at a heating temperature of 1,300°C and in a vacuum atmosphere, namely at a pressure of not higher than 10 Pa, is not more than 4% by mass relative to the sample before measurement.

2. (original) A sintered object of silicon monoxide according to Claim 1, wherein, in the thermogravimetry, the heating temperature is controlled within the range of 1,300°C ± 50°C.

3-8. canceled